

**AMENDMENTS TO THE CLAIMS**

**This listing of claims will replace all prior versions and listings of claims in the application:**

**LISTING OF CLAIMS:**

1. (canceled).
2. (previously presented): The method for producing a light-transmitting electromagnetic wave-shielding film according to claim 6, wherein the silver salt in the silver salt-containing layer is a silver halide.
3. (original): The method for producing a light-transmitting electromagnetic wave-shielding film according to claim 2, wherein the silver halide consists mainly of silver bromide.
4. (original): The method for producing a light-transmitting electromagnetic wave-shielding film according to claim 2, wherein the silver halide contains a rhodium compound and/or an iridium compound.
5. (original): The method for producing a light-transmitting electromagnetic wave-shielding film according to claim 2, wherein the silver halide contains Pd(II) ions and/or Pd metal.
6. (currently amended): A method for producing a light-transmitting electromagnetic wave-shielding film having a conductive metal portion and a light transmitting portion, which comprises  
  
exposing a silver salt-containing layer to an electromagnetic wave, wherein the silver salt-containing layer contains a silver salt and the silver salt-containing layer is provided on a support,

developing said exposed silver salt-containing layer with a development technique used for a silver salt photographic film so as to form a metal silver portion, and

subjecting the metal silver portion to physical development and/or plating to form the conductive metal portion consisting of the metal silver portion carrying conductive metal particles;

wherein the silver salt-containing layer contains Ag and a binder and has an Ag/binder ~~volume ratio of 1/4 or higher~~volume ratio of 1/1 or higher.

7. (previously presented): The method for producing a light-transmitting electromagnetic wave-shielding film according to claim 6, wherein the silver salt in the silver salt-containing layer has a diameter as sphere of 0.1 to 100 nm.

8. (previously presented): The method for producing a light-transmitting electromagnetic wave-shielding film according to claim 6, wherein the developer used for the development of the silver salt-containing layer is a lith developer.

9. (previously presented): The method for producing a light-transmitting electromagnetic wave-shielding film according to claim 6, wherein an exposed portion after the development contains the metal silver at a content of 50% by weight or more based on the weight of silver contained in the exposed portion before the exposure.

10. (previously presented): The method for producing a light-transmitting electromagnetic wave-shielding film according to claim 6, wherein the plating is performed by electroless plating.

11. (previously presented): The method for producing a light-transmitting electromagnetic wave-shielding film according to claim 6, wherein the surface of the conductive metal portion is further subjected to a blackening treatment.

12. (canceled).

13. (previously presented): The method for producing a light-transmitting electromagnetic wave-shielding film according to claim 6, wherein the light-transmitting electromagnetic wave-shielding film has a surface resistance of  $2.5 \Omega/\text{sq}$  or lower after the physical development and/or plating, and/or the light-transmitting portion has a transmittance of 95% or higher.

14-20. (canceled).

21. (previously presented): A method for producing a light-transmitting electromagnetic wave-shielding film according to claim 6, wherein the support is a plastic film, a plastic plate or a glass plate.

22. (previously presented): A method for producing a light-transmitting electromagnetic wave-shielding film according to claim 6, additionally comprising removing silver-salt from unexposed regions of the silver-salt containing layer.

23. (currently amended): A method for producing a light-transmitting electromagnetic wave-shielding film according to ~~claim 6~~ claim 2, wherein the silver halide functions as an optical sensor.

24. (previously presented): A method for producing a light-transmitting electromagnetic wave-shielding film according to claim 6, wherein the binder includes water-soluble polymers.

25. (previously presented): A method for producing a light-transmitting electromagnetic wave-shielding film according to claim 6, wherein the binder includes gelatin.

26. (previously presented): A method for producing a light-transmitting electromagnetic wave-shielding film according to claim 6, additionally comprising fixing the developed and exposed silver salt-containing layer.

27. (currently amended): A method for producing a light-transmitting electromagnetic wave-shielding film having a conductive metal portion and a light transmitting portion, which comprises

exposing a silver salt-containing layer to an electromagnetic wave, wherein the silver salt-containing layer contains a silver salt and the silver salt-containing layer is provided on a support,

developing said exposed silver salt-containing layer with a development technique used for a silver salt photographic film so as to form a metal silver portion, and

subjecting the metal silver portion to physical development and/or plating to form the conductive metal portion consisting of the metal silver portion carrying conductive metal particles;

wherein the silver salt-containing layer contains Ag and a binder and has an Ag/binder ~~volume ratio of 1/4 or higher~~volume ratio of 1/1 or higher, and

wherein the light transmitting portion does not substantially contain physical development nuclei.

28-30. (canceled).

31. (previously presented): The method for producing a light-transmitting electromagnetic wave-shielding film according to claim 6, wherein the light-transmitting electromagnetic wave-shielding film has an aperture ratio of 85 % or higher.